

1. Chemical Vapor Deposition System (MEL 2218)

RMR-2000 series thermal chemical vapor deposition (CVD) system for graphene synthesis.

Features:

- Argon (Ar), methane (CH₄) and hydrogen (H₂) gases with controlled flowrate.
- Three temperature zones with three independent controllers.
- Variable vacuum range; vacuum pressure lower than 1 mTorr can be achieved.
- Rapid heating and wide temperature range. For graphene synthesis, the substrate is heated up to 1050 °C in the time interval of 45 min.
- Digital displays show actual wafer temperature, chamber pressure, as well as gas flow rate.

